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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/685,751	10/14/2003	Yong Liu	NTI-023-1D 6170	
29477	7590 04/01/2004		EXAM	INER
BEVER HOFFMAN & HARMS, LLP		LP	ROSASCO, STEPHEN D	
	ANNON BLVD		ART UNIT	PAPER NUMBER
BLDG G	*: • **		ARTONII	TATER NUMBER
LIVERMORI	E CA 94550-6006		1756	

DATE MAILED: 04/01/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

····	· · · · · · · · · · · · · · · · · · ·	Application No.	Applicant(s)			
	a.					
Office Action Summary		10/685,751	LIU ET AL.			
	Office Action Summary	Examiner	Art Unit			
	THE MAN INC DATE SALE	Stephen Rosasco	1756			
Period fo	The MAILING DATE of this communication app r Reply	ears on the cover sheet with the c	orrespondence address			
THE N - Extendent after in the control of the contr	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Is ions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period we to reply within the set or extended period for reply will, by statute, eply received by the Office later than three months after the mailing of patent term adjustment. See 37 CFR 1.704(b).	6(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status		- '				
1) 💢	Responsive to communication(s) filed on 14 Oc	ctober 2003.				
<u> </u>		action is non-final.				
3)[_						
	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Dispositi	on of Claims					
	· ·					
,	Claim(s) <u>1-5</u> is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration.					
4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) is/are allowed.						
	Claim(s) <u>1-5</u> is/are rejected.		•			
	Claim(s) are subject to restriction and/or	election requirement.				
Annlicati	on Papers	ė.				
		. **				
9) The specification is objected to by the Examiner.						
10)⊠ The drawing(s) filed on <u>14 October 2003</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.35(a).					
	The oath or declaration is objected to by the Ex		• •			
	nder 35 U.S.C. § 119					
1.0	χ,		· - 100 - 12 - 1			
12) Acknowledgment is made of a claim for föreign priority under 35 U.S.C. § 119(a)-(d) or (f).						
a) All b) Some * c) None of:						
 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 						
3. Copies of the certified copies of the priority documents have been received in this National Stage						
application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
Ättachment	(s)		•			
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)						
	e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	Paper No(s)/Mail Da 5) Notice of Informal P	ate atent Application (PTO-152)			
	No(s)/Mail Date <u>10/14/03</u> .	6) Other:				

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Detailed Action

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-5 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ferguson et al. (5,932,377).

The claimed invention is directed to a lithographic mask that provides phase shifting for features 6n a binary mask, the lithographic ma/k comprising: a plurality of first phase-shifting regions; and a plurality of second phase-shifting regions, wherein each first phase-shifting region has a corresponding second phase-shifting region, wherein a phase difference between the first and second phase-shifting regions is approximately 180 degrees, wherein each second phase-shifting region has a size based on a size of its corresponding first phase-shifting region.

Ferguson et al. teach a two-step method for eliminating transmission errors in alternating phase-shifting masks. Initially, the design data is selectively biased to provide a coarse reduction in the inherent transmission error between features of different phase, size, shape, and/or location. During fabrication of the mask with the modified data, residual transmission errors are then eliminated via the positioning of the

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edges of the etched-quartz trenches, which define the phase of a given feature to a set location beneath the opaque chrome film.

(col. 6, line 50 to col. 7, line 15) Referring to FIG. 7, transmission error between two adjacent features of opposite phase is quantified in the plot shown in FIG. 7 as a function of the coarse tuning via biasing of the design data (curve-to-curve variation) and fine tuning with the etch-back process (change in transmission error along one curve). A transmission error of 0% is the ideal value at which the two features are completely balanced. In FIG. 7, data point 100 represents the transmission error (approximately 28%) when no coarse or fine adjustments are applied. A displacement along the y-axis (etch back depth=0 nm) from data point 100 représents a change in transmission error from the coarse bias adjustment. For the design grid size of 25 nm used in this example, the effect of a coarse adjustment of one grid unit is to reduce the transmission error to 10% (i.e., at data point 110). For a two-grid step bias of 50 nm, the transmission error is over-corrected at data point 120. Thus, biasing the design data by a single grid step of 25 nm to point 110 provides the appropriate coarse adjustment to the transmission error. Three data points 111, 112, and 113 (in FIG. 7) show the effect of varying the etch back depth in order to remove the residual transmission error after completing the coarse adjustment.

The teachings of Ferguson et al. differ from those of the applicant in that the applicant teaches that each second phase-shifting region has a size based on a size of its corresponding first phase-shifting region. However, Ferguson et al. does teach that initially, the design data is selectively biased to provide a coarse reduction in the

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inherent transmission error between features of different phase, <u>size</u>, shape, and/or location.

Therfore, it would have been obvious to one having ordinary skill in the art to take the teachings of Ferguson et al. and adjust the size of one phase shifting region based on the size of the other phase shifting region in order to make the claimed invention because it is well known in the phase shifting art that the size and spacing of the shifters in a mask must be such that these phase shift regions do not produce phase conflicts.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stephen Rosasco whose telephone number is 571-272-1389. The examiner can normally be reached on M-F from 9 to 5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff, can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

For general Information call (571-272-1700).

S. Rosasco

Primary Examiner

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S.Rosasco 3/25/04